

# コーティング内で発生する位相ズレによる波面誤差について

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Technology in Astronomy

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- In background-limited observations,

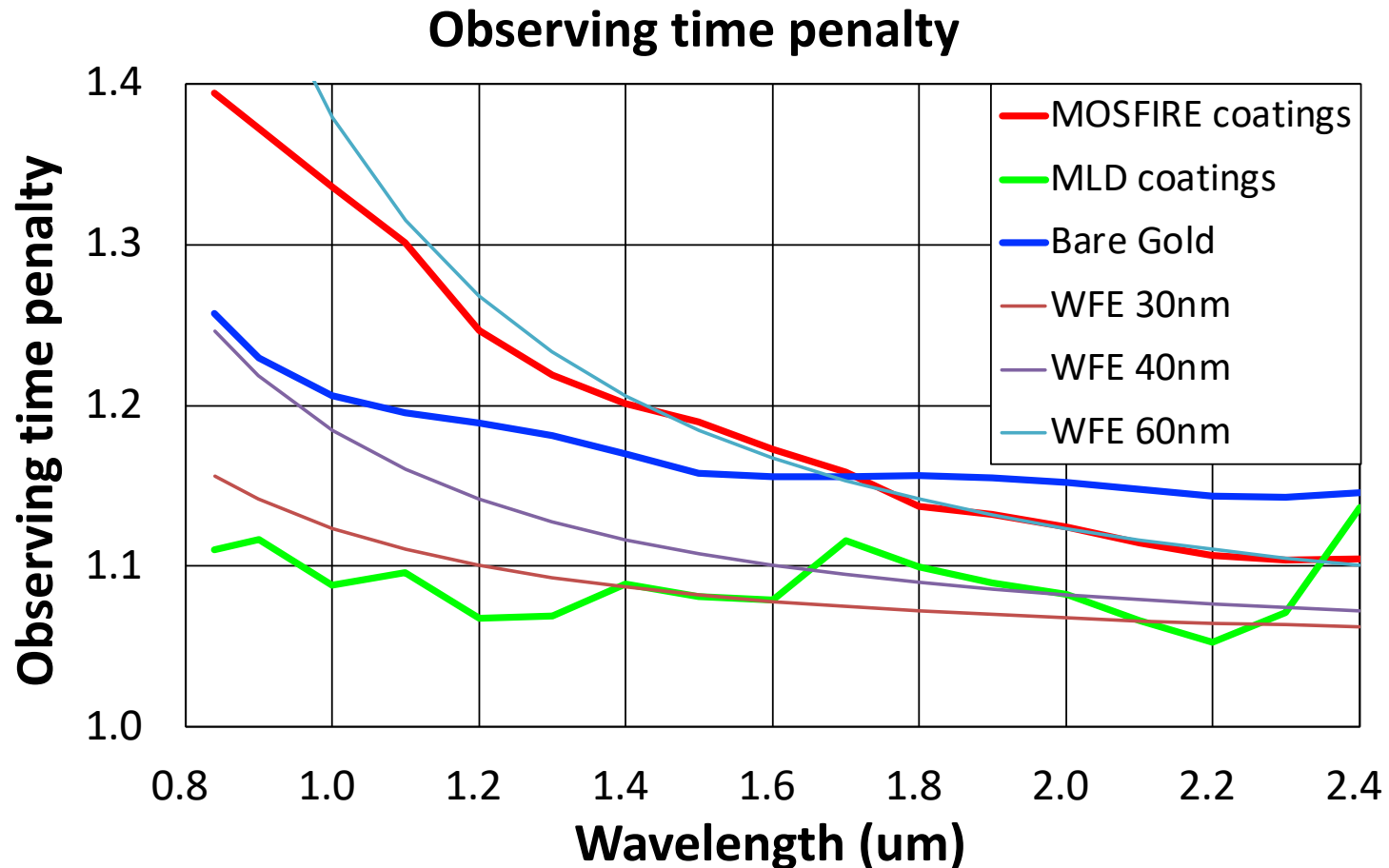
$$S/N = \frac{C_{obj}}{\sqrt{\sigma_{obj}^2 + \sigma_{bg}^2 + \sigma_{dark}^2 + \sigma_{read}^2}} \sim \frac{C_{obj}}{\sigma_{bg}} = \frac{f_{obj}\epsilon t}{\sqrt{\frac{f_{bg}}{\int \varphi_{(\theta)}^2 d\Omega} \epsilon t}} = \sqrt{\frac{f_{obj}^2 \epsilon t \int \varphi_{(\theta)}^2 d\Omega}{f_{bg}}}$$

$$\text{Point Source Sensitivity} \equiv \frac{1}{t} \propto \epsilon \int \varphi_{(\theta)}^2 d\Omega \sim \epsilon SR^2$$

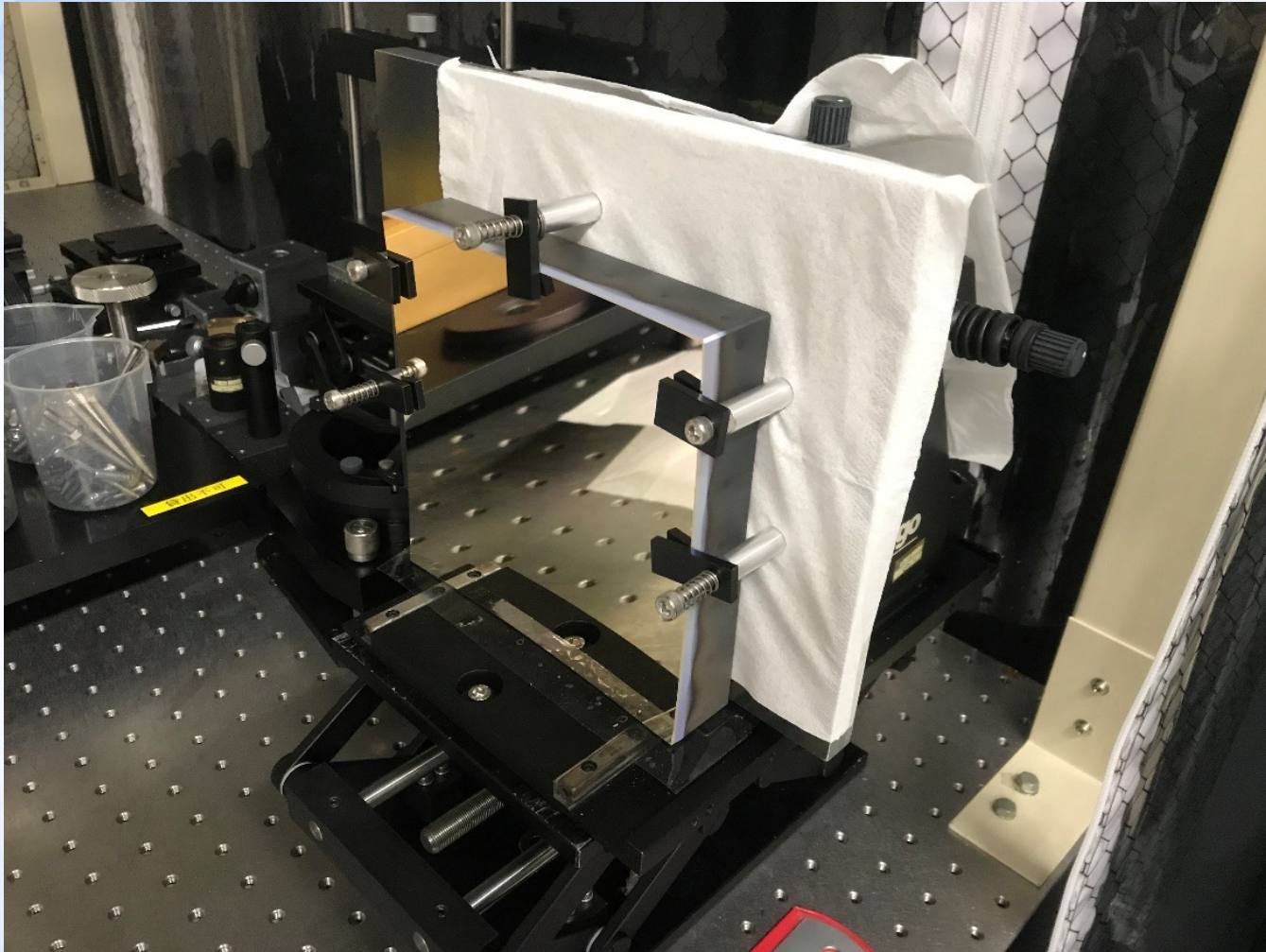
throughput
PSF profile
Strehl Ratio ← Wavefront error

- MLD coatings provide higher throughput, but thicker MLD coatings are expected to induce stress (deformation) on the mirror surface, i.e., wavefront error.

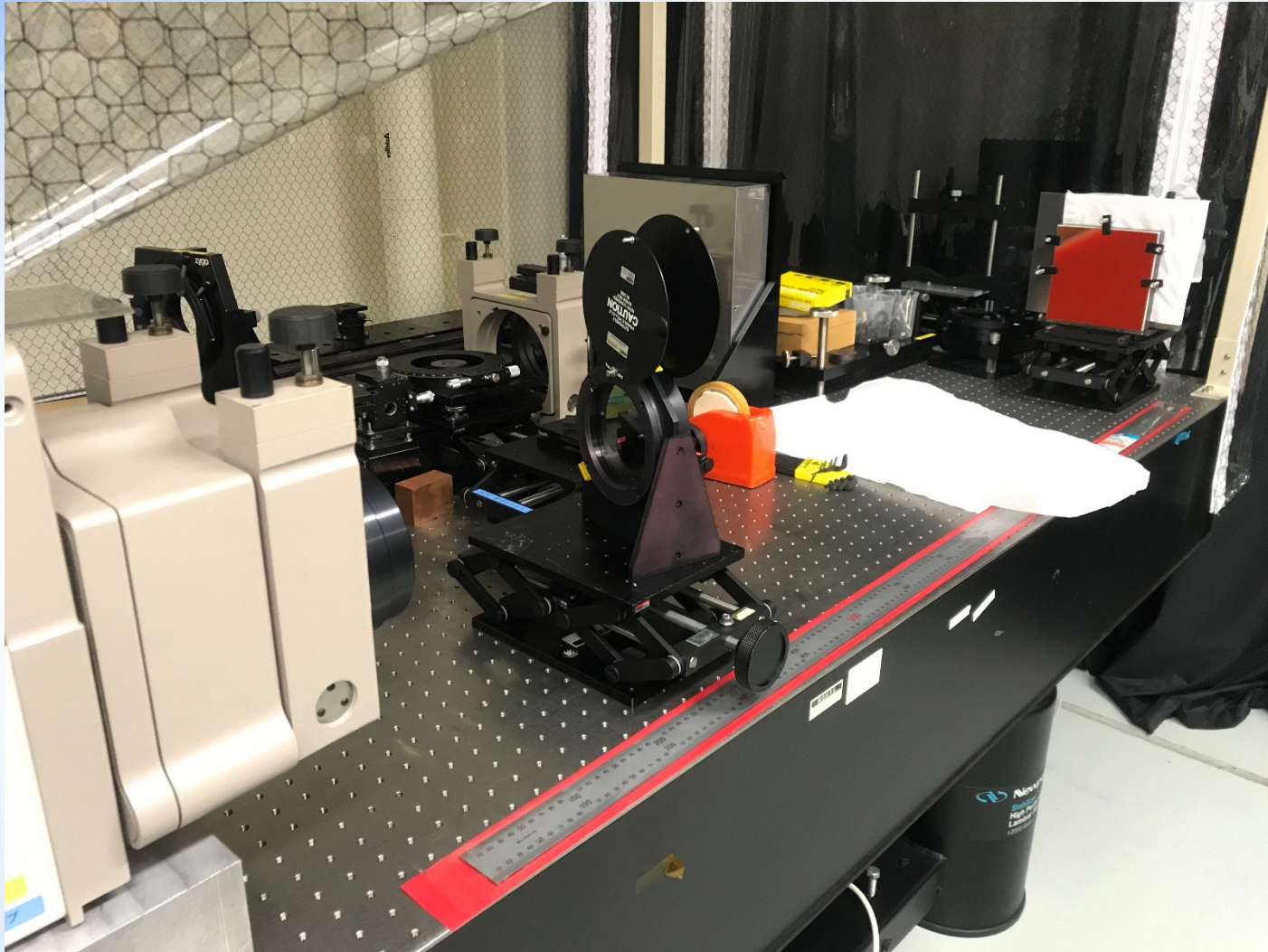
# Point Source Sensitivity



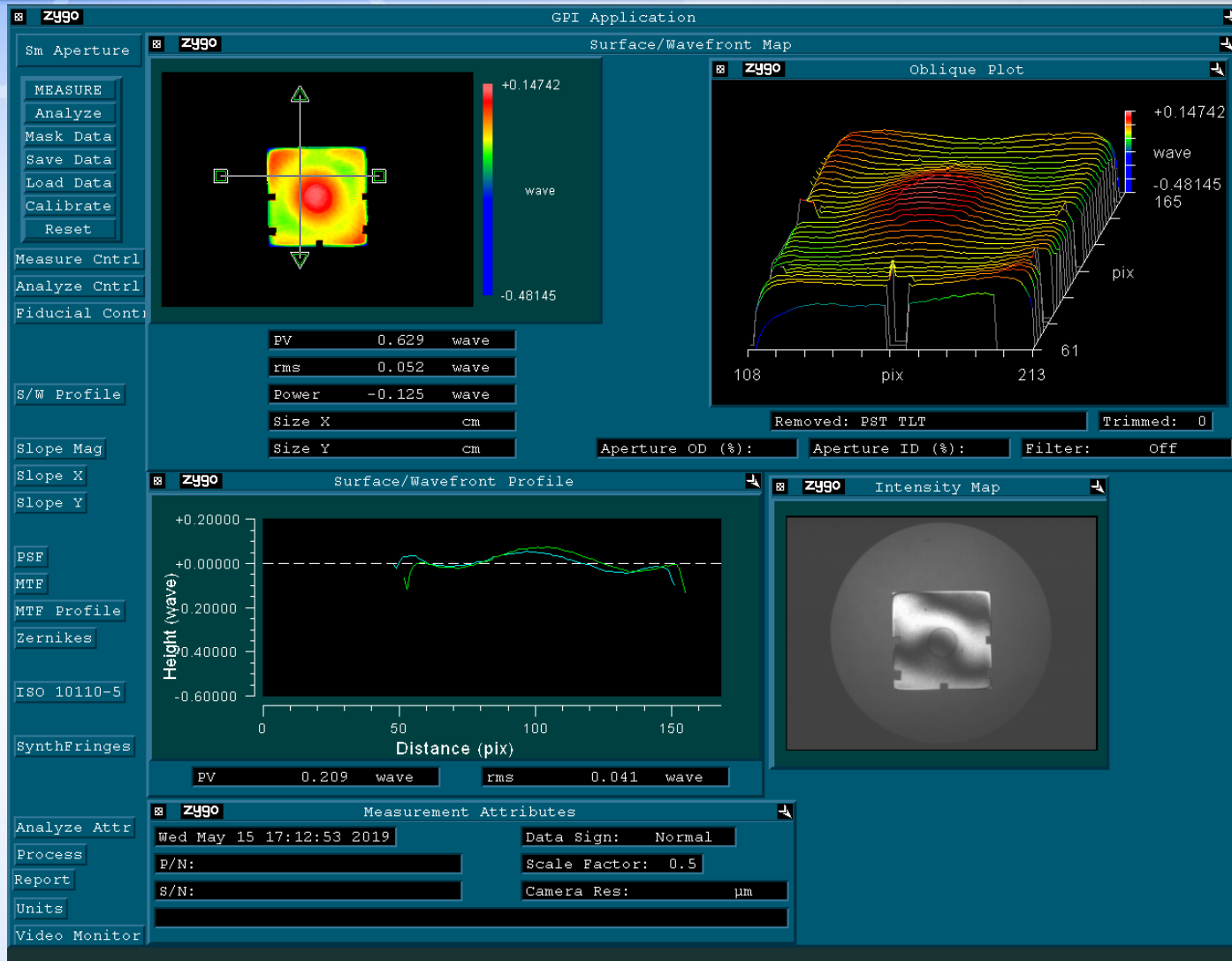
# Prototyped concave mirror



# Interferometer set up

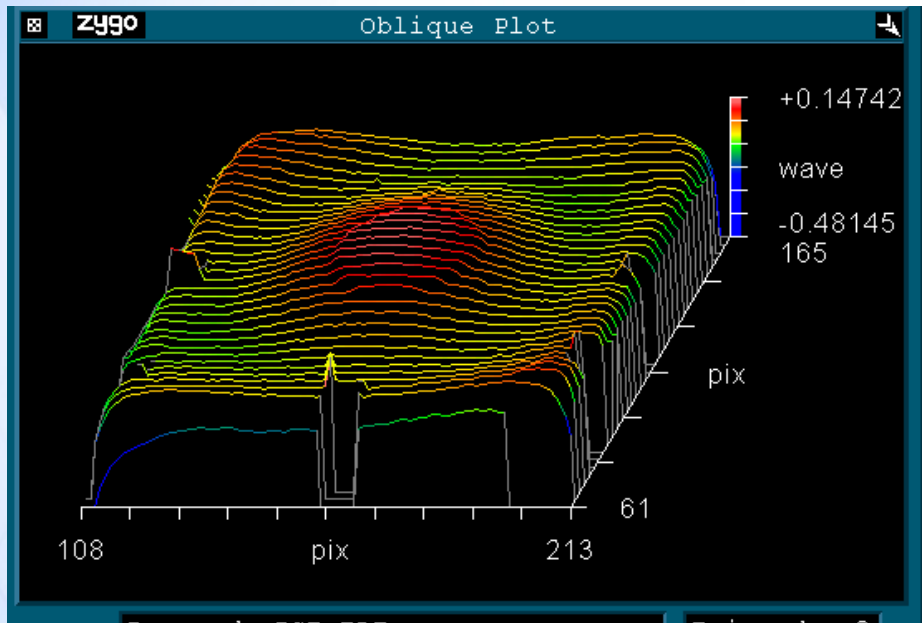
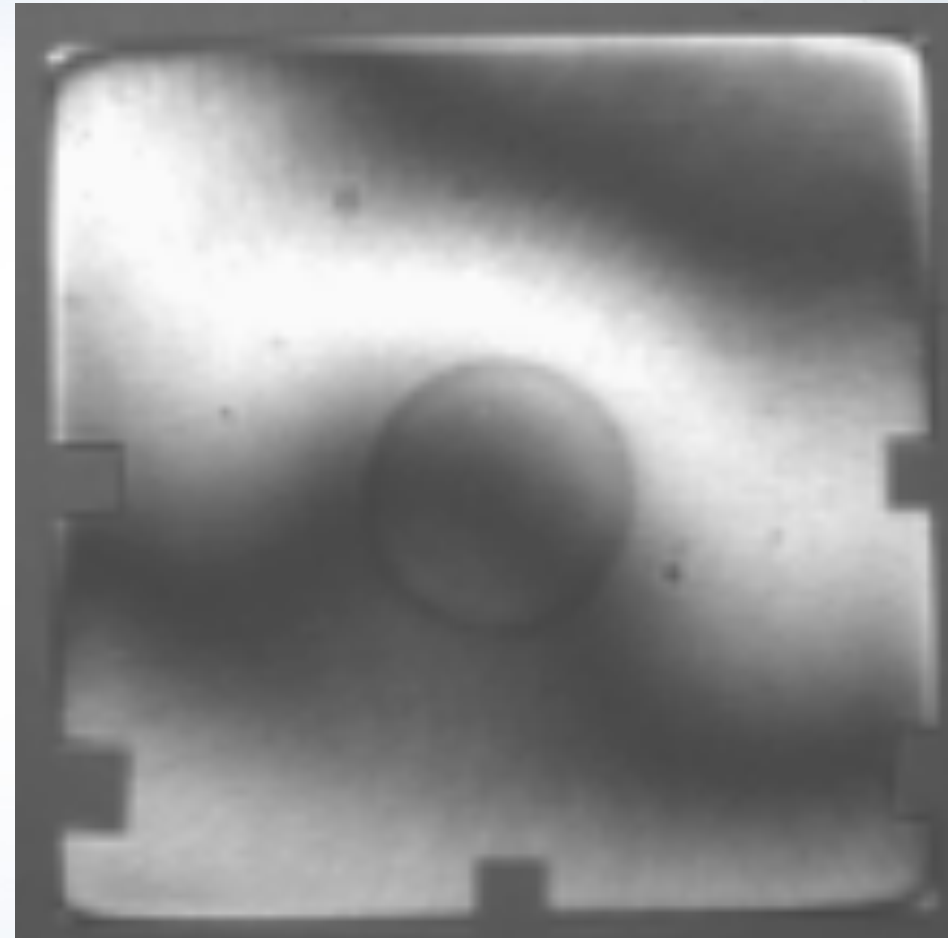


# Surface shape measurement results



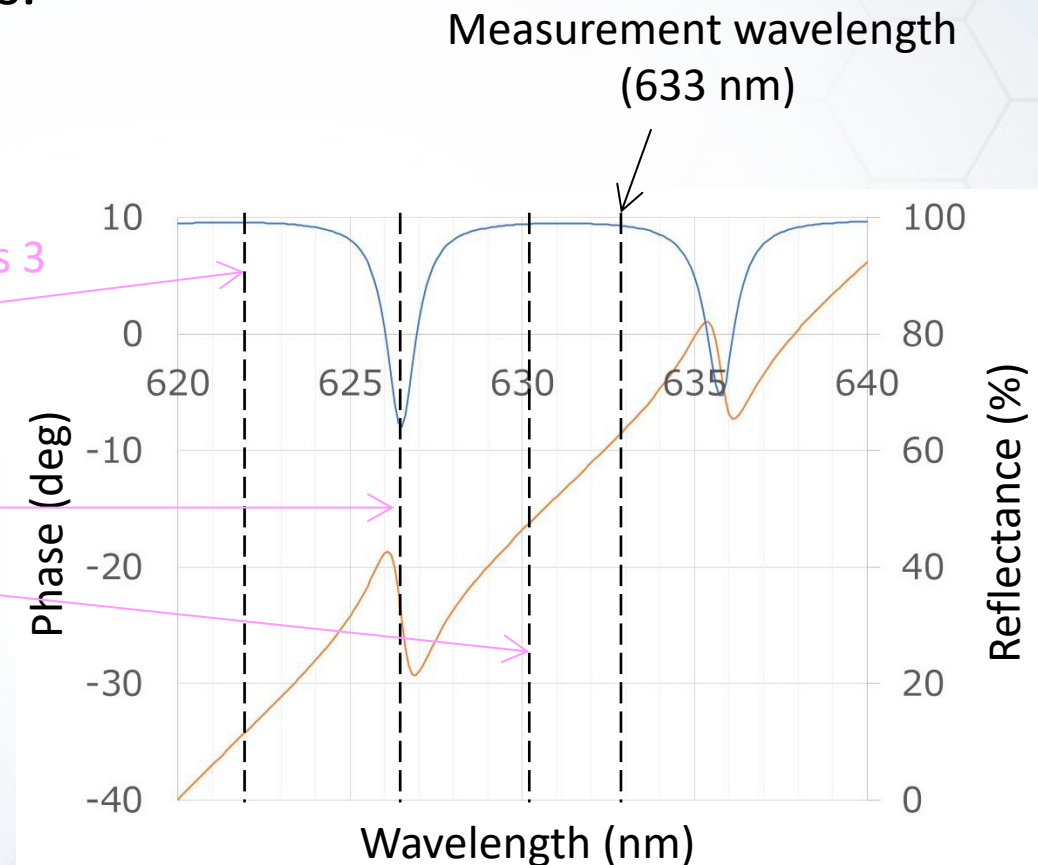
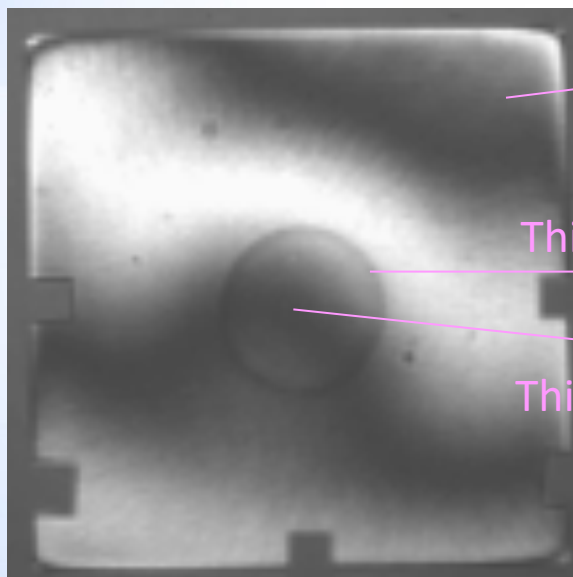
# Surface shape measurement results

- ◆ Island pattern
  - ◇ 50 mm dia.
  - ◇ 20 – 30 nm height

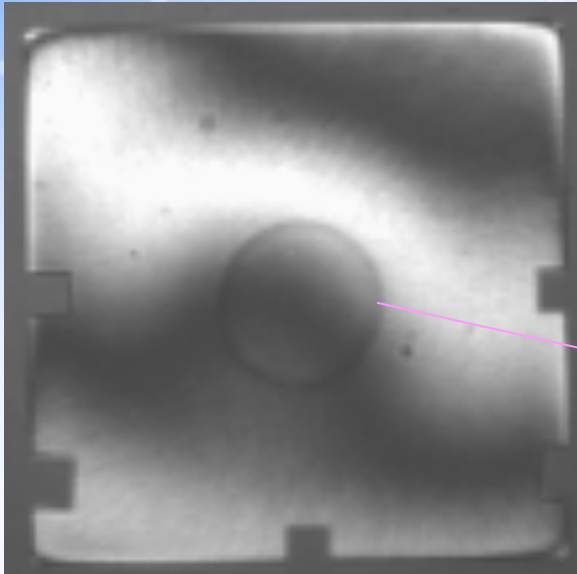


# Vendor's model

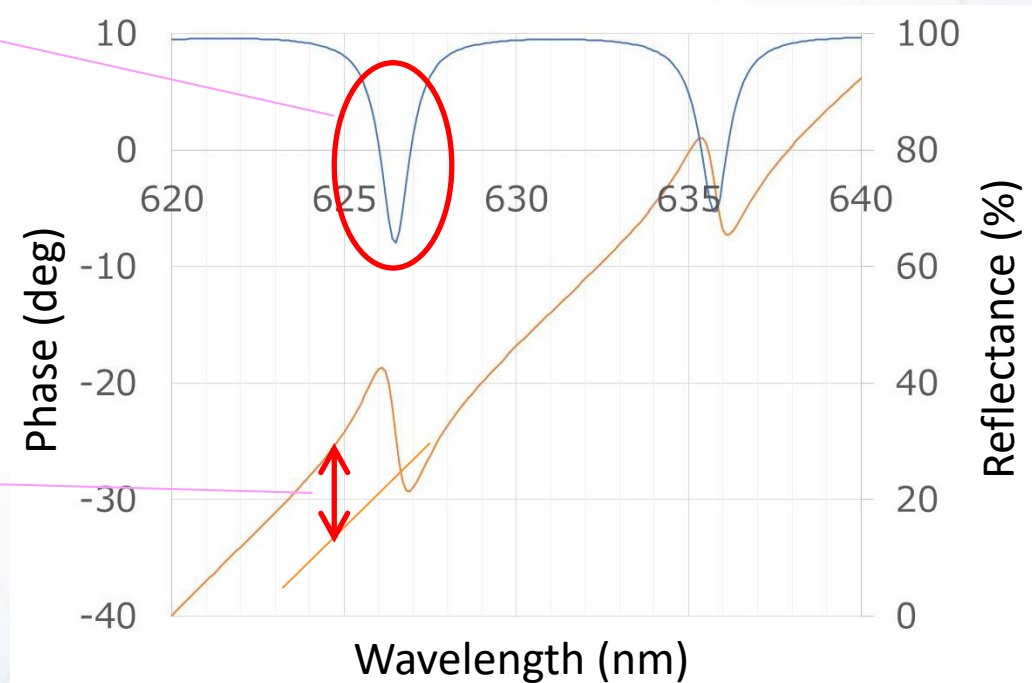
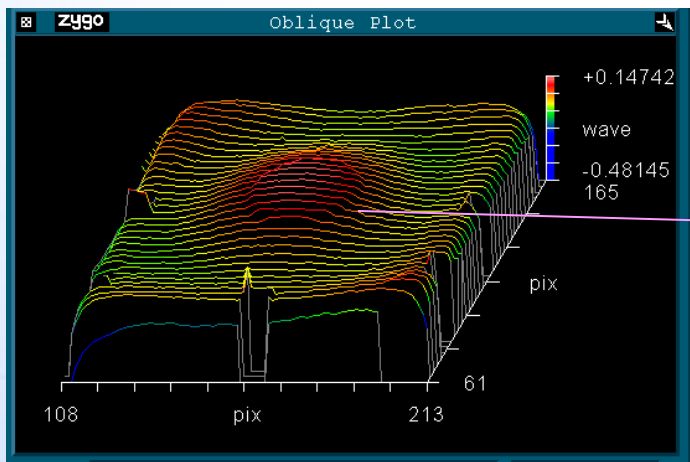
- The phase and R profile shifts along the wavelength if the coating thickness changes.



# Vendor's model

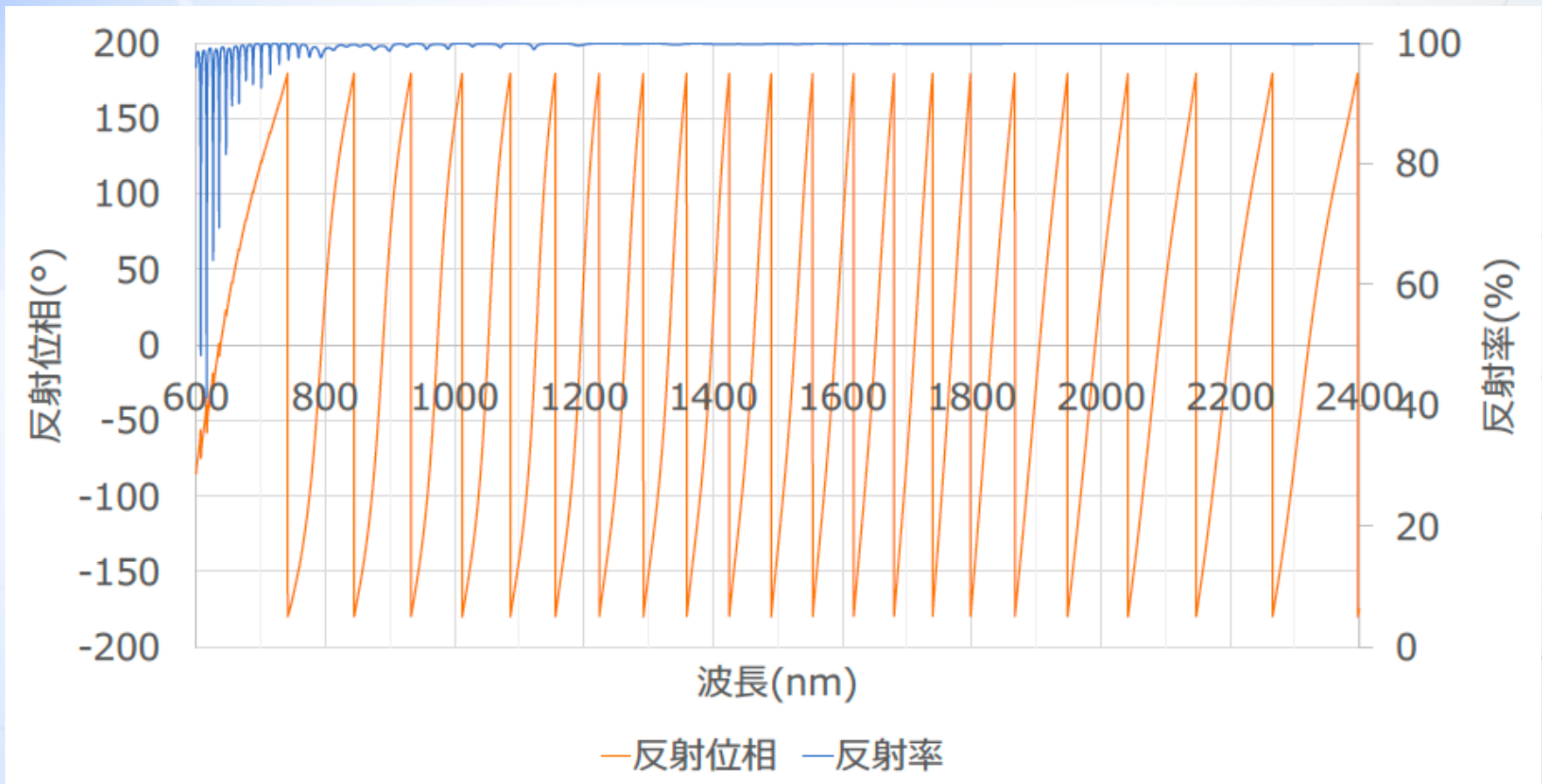


- ◆ We have some other measurements to support the model.



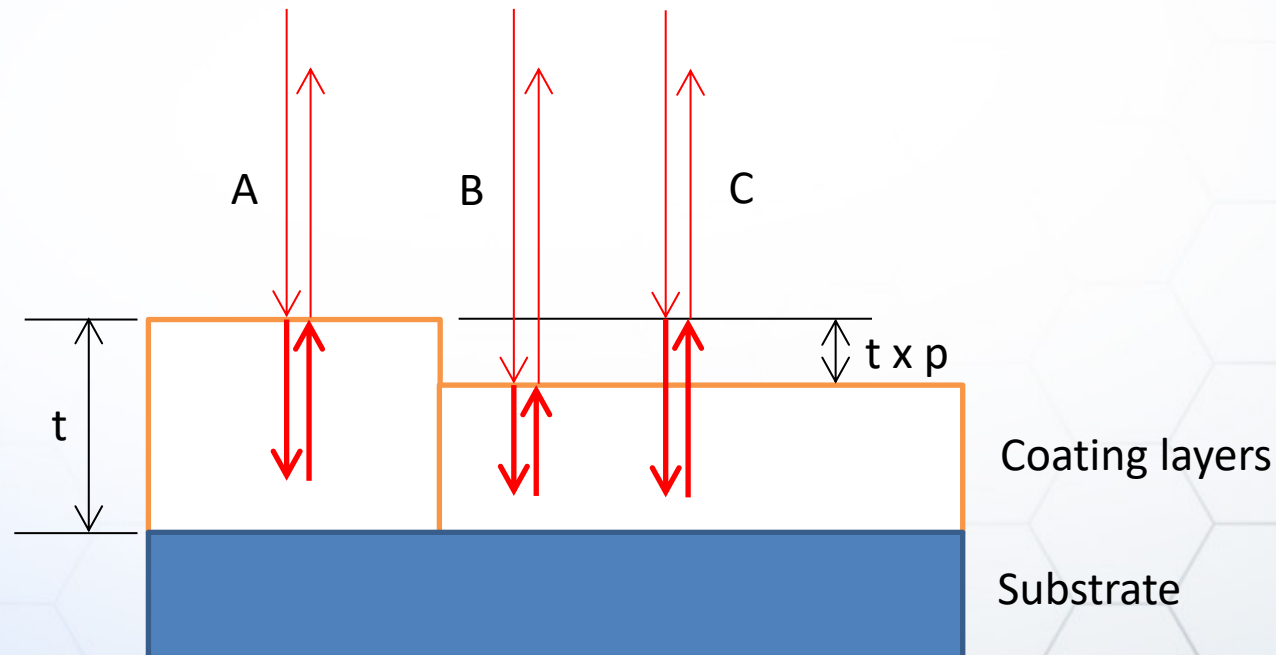
# Vendor's model

- ◆ The phase changes a lot along the wavelength



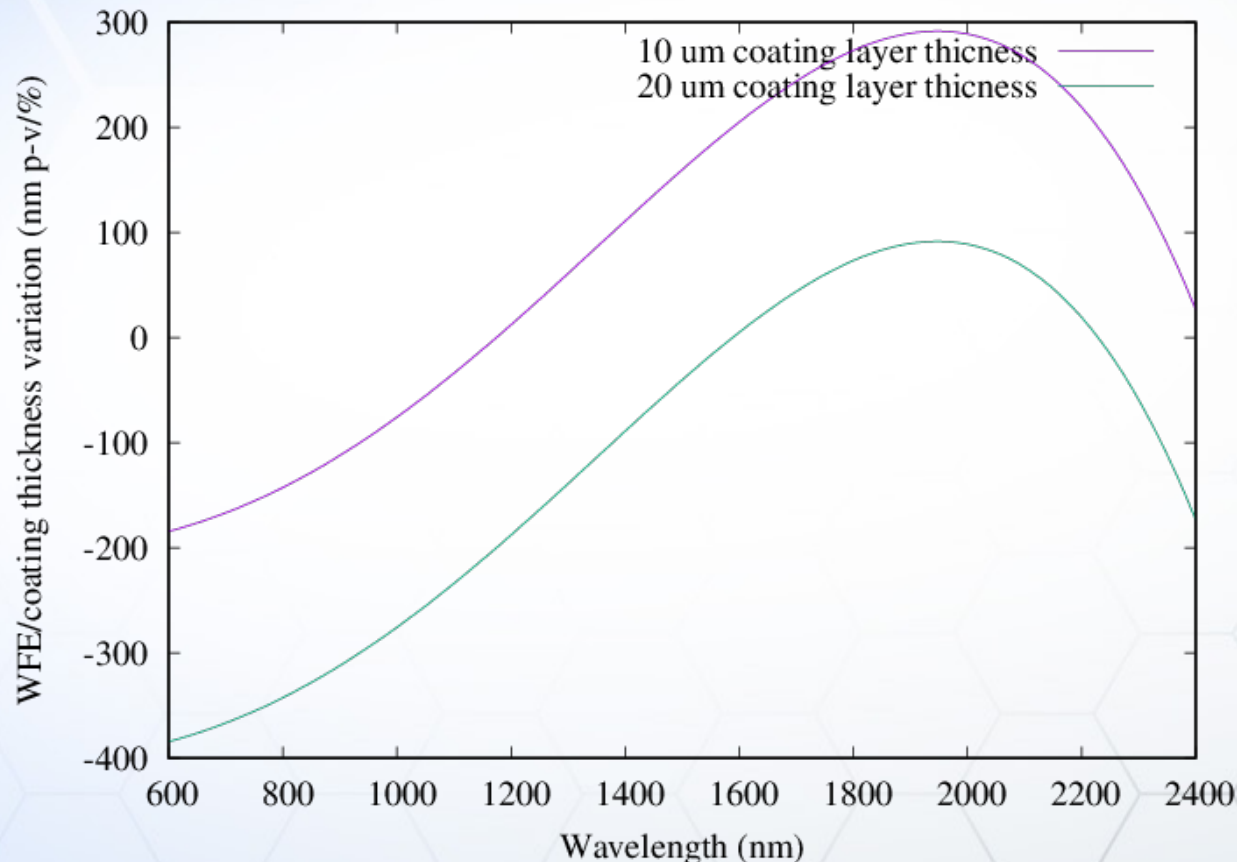
# Calculation (WFE/non-uniformity)

- I calculated an optical path difference between A and C for different non-uniformity % (p).



# Results for MLD coatings (WFE/non-uniformity)

- 1% coating non-uniformity results in 400 nm p-v WFE which is of course intolerable, c.f. 5 – 10 nm p-v WFE per surface



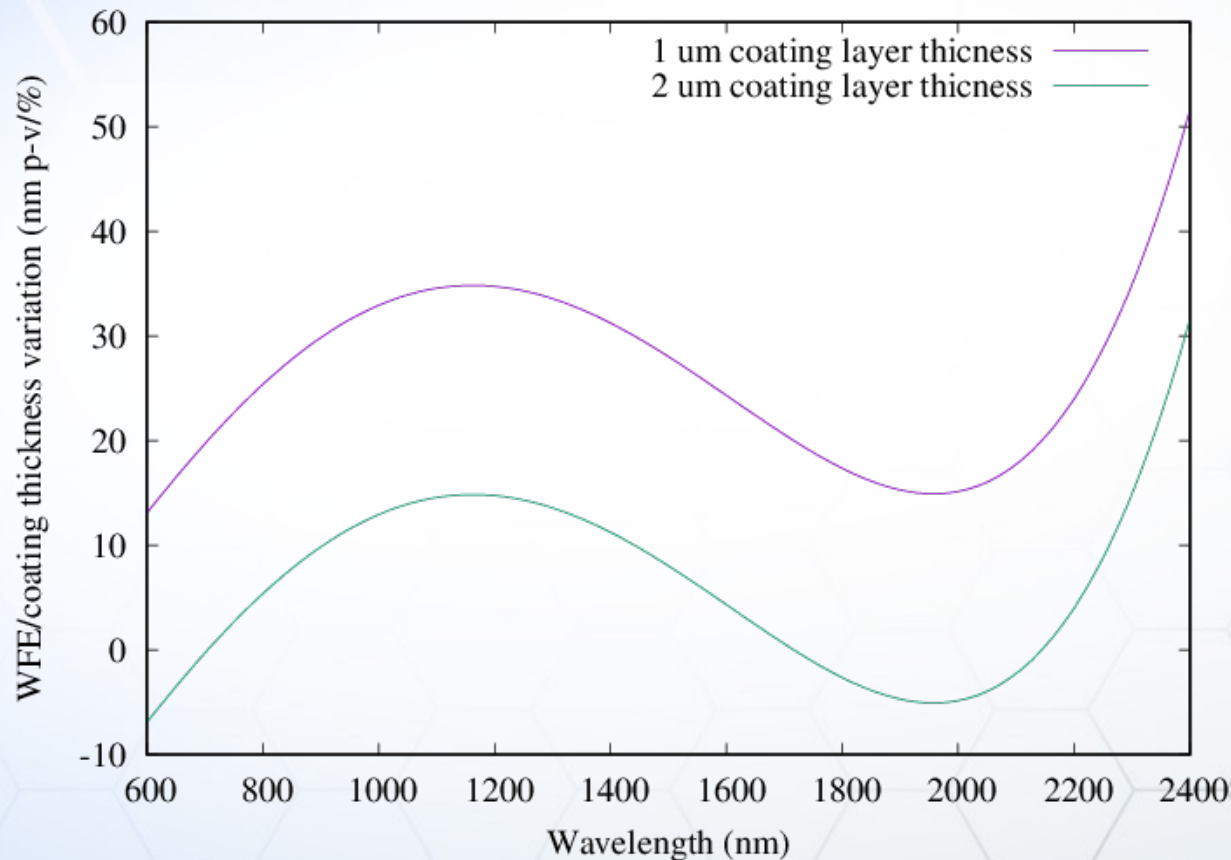
# Discussions

- The vendor expects 2% non-uniformity for the prototyped mirror substrate.
- The phase shift due to the coating thickness non-uniformity may be compensated by DMs if it has a low order pattern (up to 2<sup>nd</sup> order).
  - But the non-uniformity pattern depends on multiple parameters like geometry of the coating gun and the substrate, substrate size and shape, and rotary motion of the substrate.

- ◆ We may be able to measure the non-uniformity pattern by measuring the reflectance pattern. (Venancio 2016. See later in the slides)
  - ◇ The coating vendor said that it is impractical to achieve uniformity at 0.01 % level.
  - ◇ Since a single layer of SiO<sub>2</sub> is known to be ~0.2 nm compared to ~170 nm which is  $\lambda/4$  thickness, non-uniformity at best is ~0.1%.

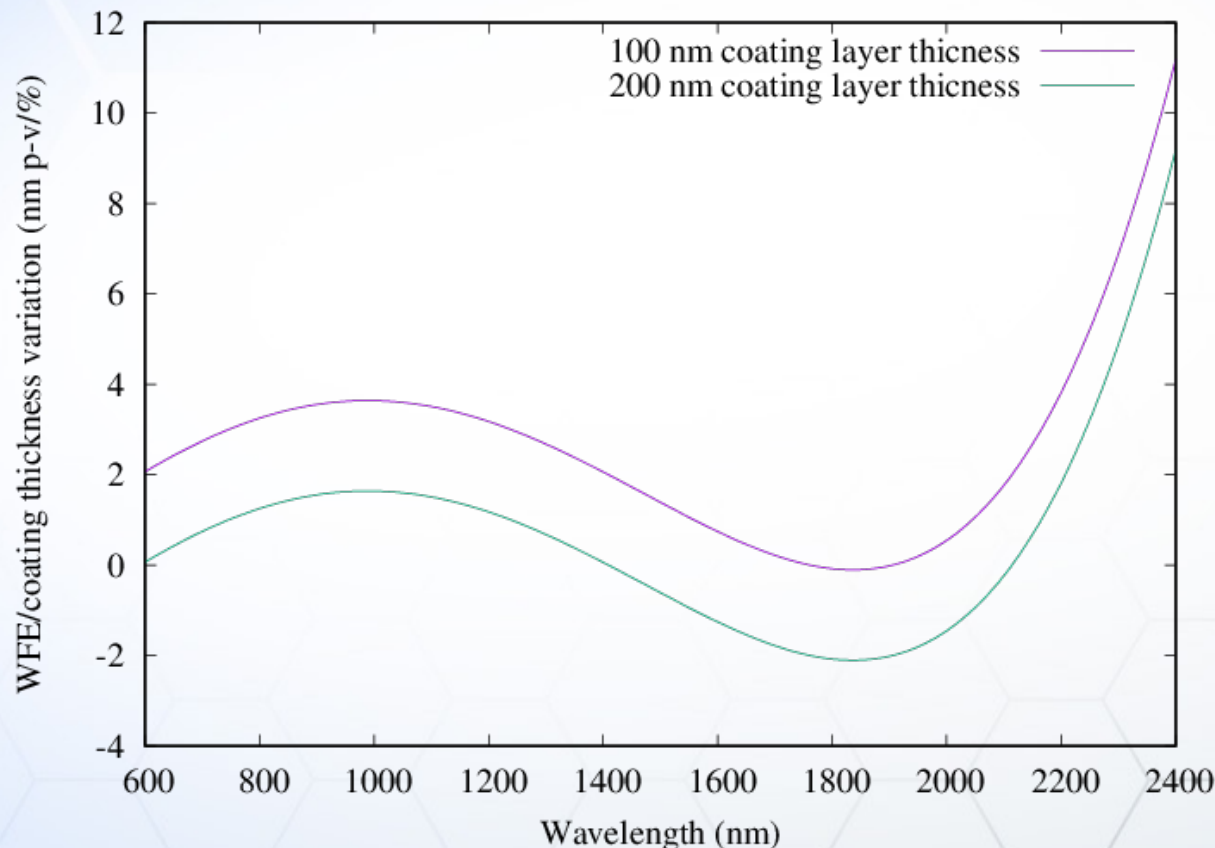
# Results for eAg coatings (WFE/non-uniformity)

- Enhanced silver (eAg) coatings have some MLD coatings over a silver layer. 1% non-uniformity results in 35 nm p-v WFE.



# Results for pAg coatings (WFE/non-uniformity)

- Protected silver (pAg) coatings have a single SiO<sub>2</sub> layer over a silver layer. 1% non-uniformity results in 11 nm p-v WFE.



# PSS comparison

|             | 誘電体<br>多層膜 | 増反射膜＋<br>銀 | 保護膜＋<br>銀 | AR coating<br>on CaF2 | 単位     |
|-------------|------------|------------|-----------|-----------------------|--------|
| WFE         | 438.0      | 33.0       | 1.2       | 11.8                  | nm p-p |
| TPmax       | 1.000      | 0.996      | 0.989     | 0.998                 | %/100  |
| TPmin       | 0.987      | 0.985      | 0.976     | 0.988                 | %/100  |
| TPave       | 0.998      | 0.991      | 0.985     | 0.996                 | %/100  |
| PSS (WFE)   | 0.546      | 0.997      | 1.000     | 1.000                 |        |
| PSS (TP)    | 0.998      | 0.991      | 0.985     | 0.992                 |        |
| PSS/element | 0.545      | 0.987      | 0.985     | 0.991                 |        |

誘電体膜を使用する際は、  
反射(透過)位相の計算を忘れずに。

# Acknowledgments

The TMT Project gratefully acknowledges the support of the TMT collaborating institutions. They are the California Institute of Technology, the University of California, the National Astronomical Observatory of Japan, the National Astronomical Observatories of China and their consortium partners, the Department of Science and Technology of India and their supported institutes, and the National Research Council of Canada. This work was supported as well by the Gordon and Betty Moore Foundation, the Canada Foundation for Innovation, the Ontario Ministry of Research and Innovation, the Natural Sciences and Engineering Research Council of Canada, the British Columbia Knowledge Development Fund, the Association of Canadian Universities for Research in Astronomy (ACURA), the Association of Universities for Research in Astronomy (AURA), the U.S. National Science Foundation, the National Institutes of Natural Sciences of Japan, and the Department of Atomic Energy of India.